Stamp fabrication

+ BHF dip

+ Spinning of SU8 2005+PGMEA (1:2)

Spinning: 2000 rpm gives apx. 460nm

Soft bake: 60sec@90C

+ Exposure with MLA 150. 375nm source. Dose 700mJ/cm2, Focus: -4

+ Post Exposure Bake 120sec@ 90C

+ Developing in PGMEA: First 4min+ Fine 1min.

+ Profilometer measurement. Stamp height apx. 280nm